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(12) **United States Design Patent**
Zeng

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(54) **FACE MASK**

(71) Applicant: **YIWU YAOCHUN NETWORK TECHNOLOGY CO., LTD.**, Yiwu (CN)

(72) Inventor: **Yangfeng Zeng**, Yiwu (CN)

(73) Assignee: **YIWU YAOCHUN NETWORK TECHNOLOGY CO., LTD.**, Yiwu (CN)

(**) Term: **15 Years**

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(51) **LOC (13) Cl.** **29-02**

(52) **U.S. Cl.**
USPC **D24/110.1**

(58) **Field of Classification Search**
USPC D24/110–110.4, 127–128, 164; D29/108, D29/110–111, 129
CPC A61M 16/06; A61M 16/0622; A41D 13/1138; A41D 13/1107; A41D 13/11; A41D 13/113; A62B 18/025; A62B 23/025; A62B 18/02; A62B 7/10; A62B 18/10; A62B 18/00; A62B 23/00; A62B 23/02
See application file for complete search history.

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Primary Examiner — Lilyana Bekic

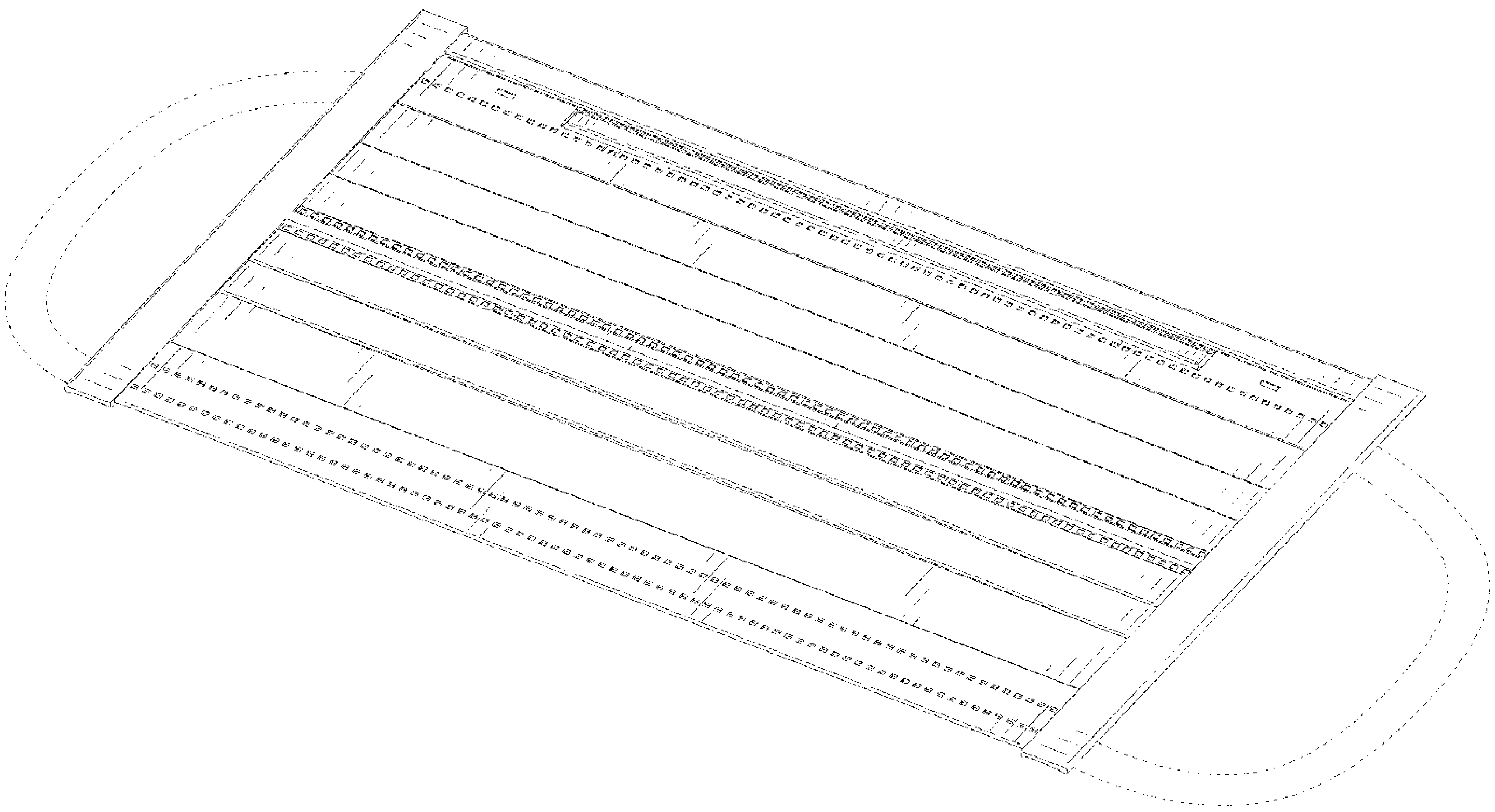
(57) **CLAIM**

The ornamental design for a face mask, as shown and described.

DESCRIPTION

FIG. **1** is a perspective view of a face mask showing my new design;
FIG. **2** is another perspective view thereof;
FIG. **3** is a front elevational view thereof;
FIG. **4** is a rear elevational view thereof;
FIG. **5** is a left side elevational view thereof;
FIG. **6** is a right side elevational view thereof;
FIG. **7** is a top plan view thereof; and,
FIG. **8** is a bottom plan view thereof.
The broken lines in the drawings depict portions of the face mask that form no part of the claimed design.

1 Claim, 8 Drawing Sheets



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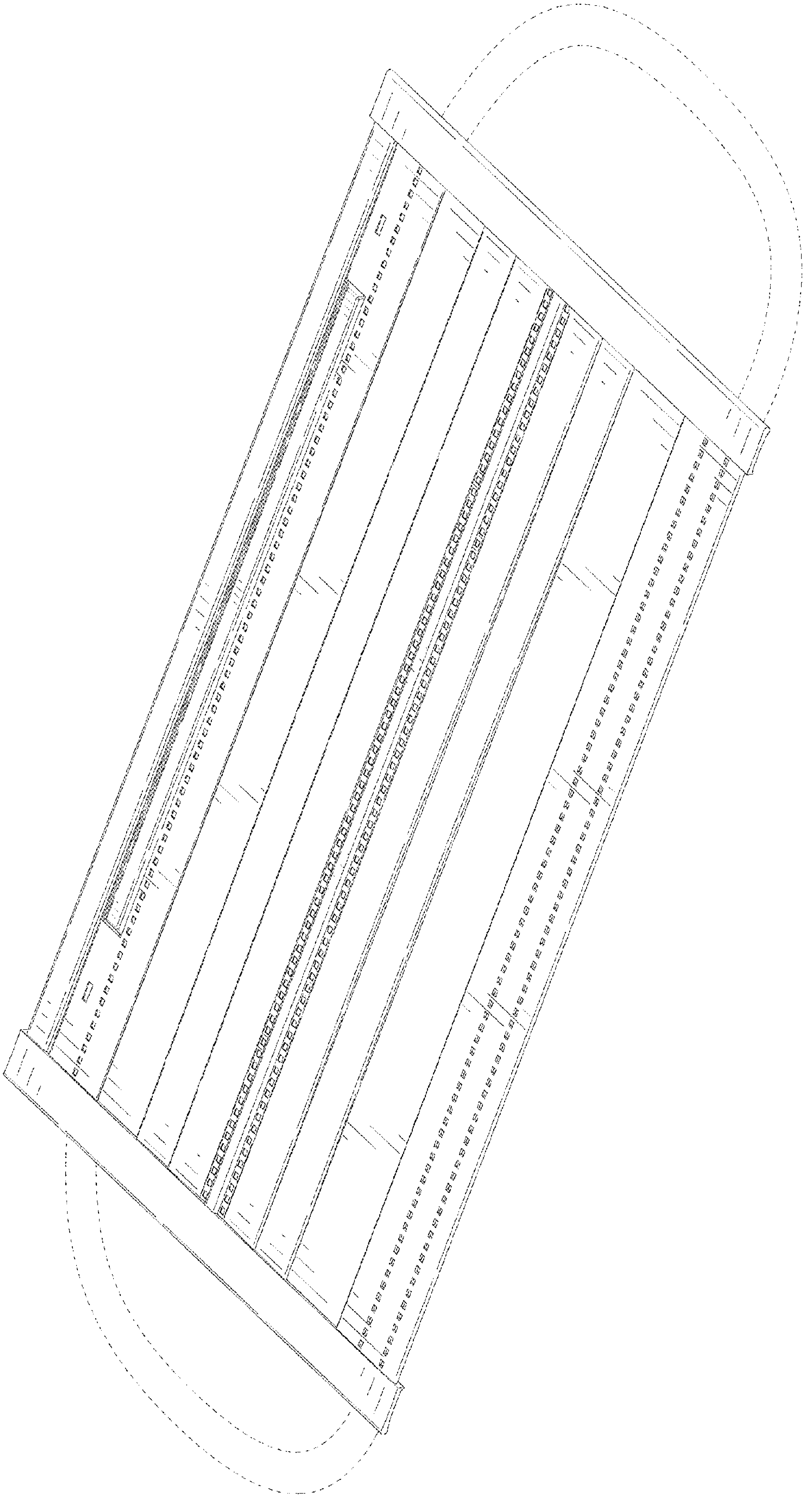

FIG. 1

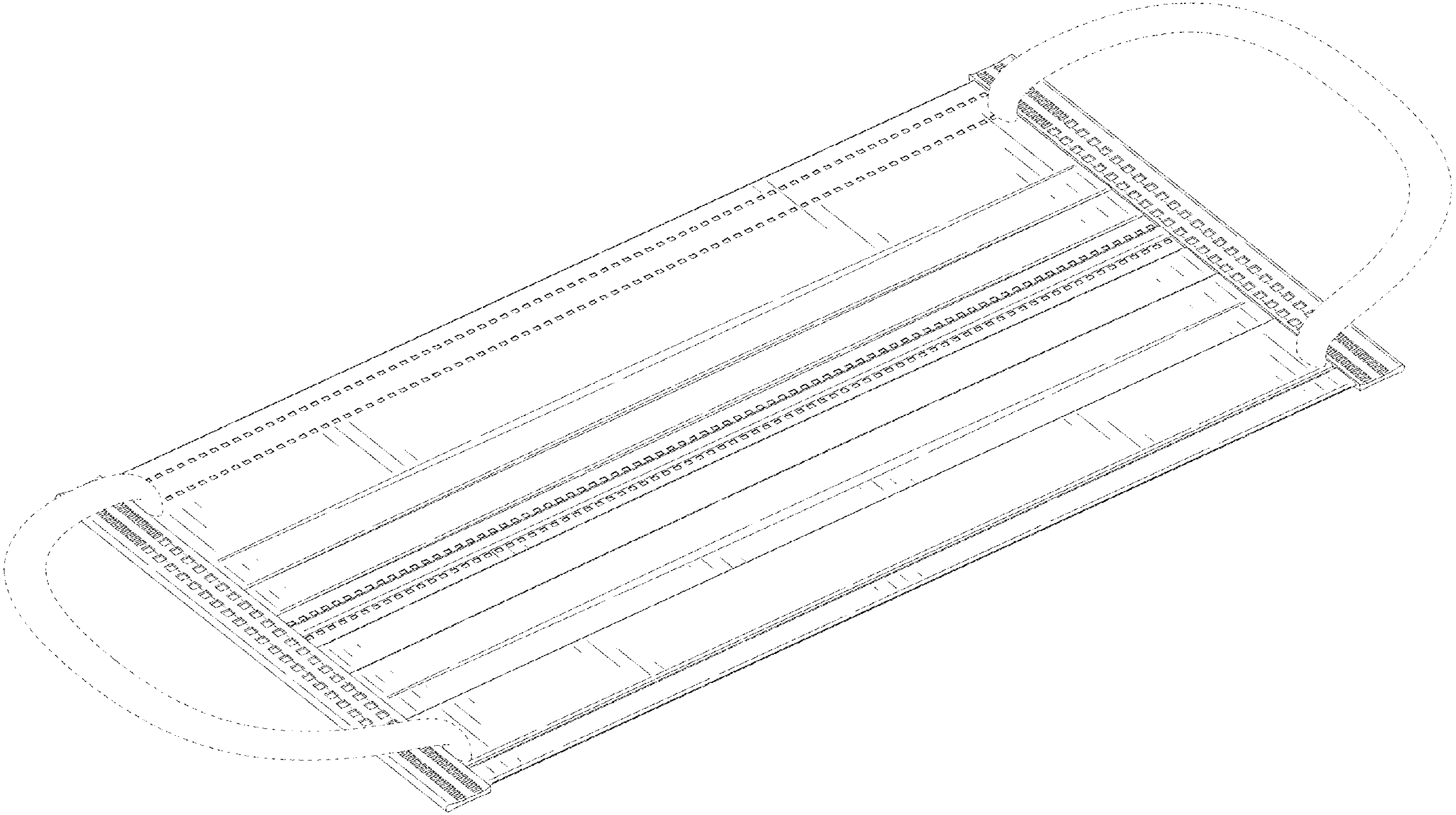

FIG. 2

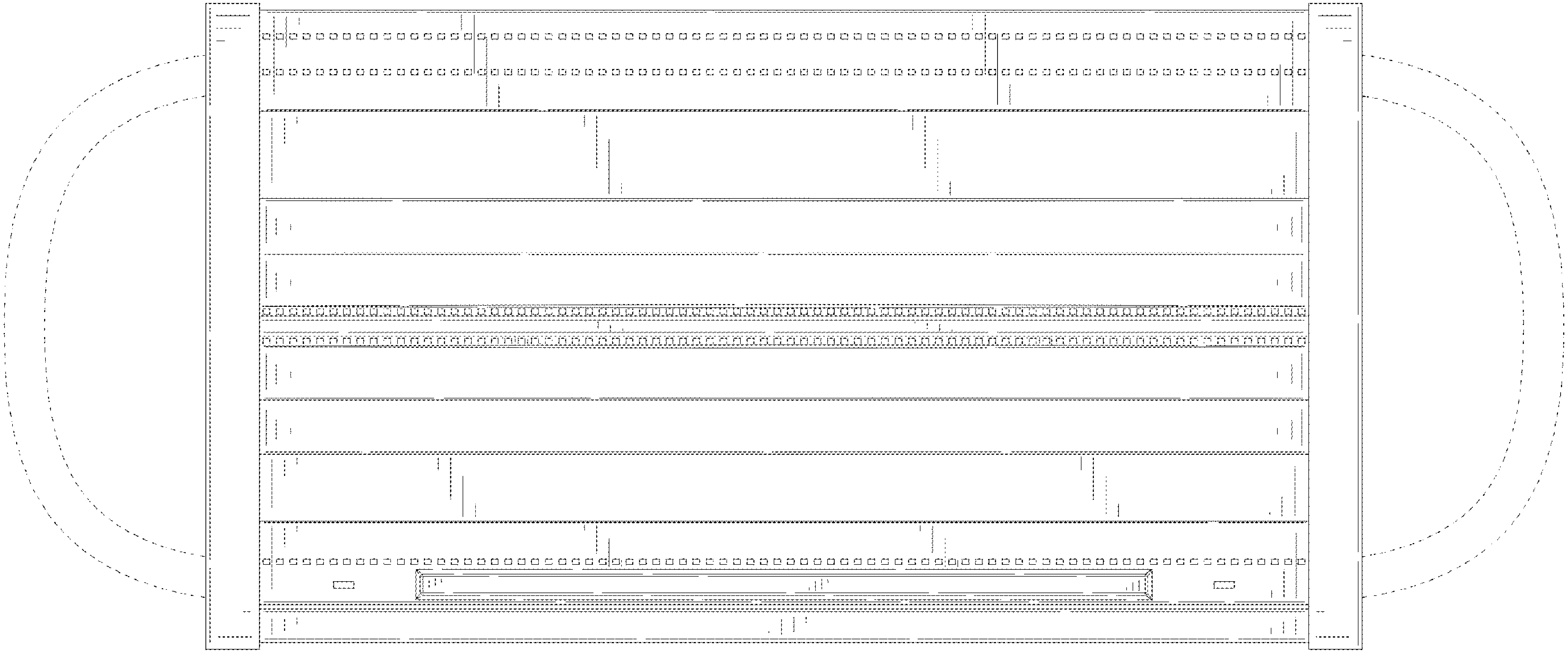

FIG. 3

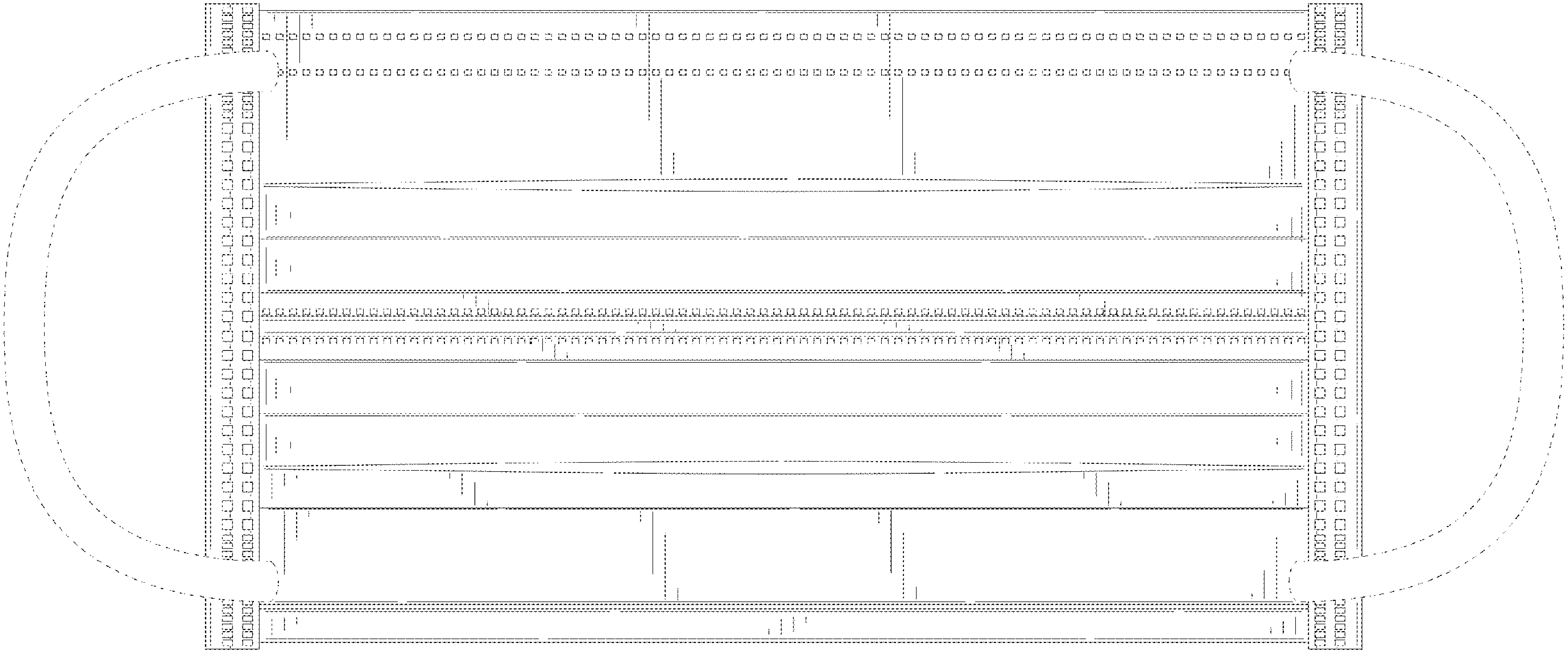

FIG. 4

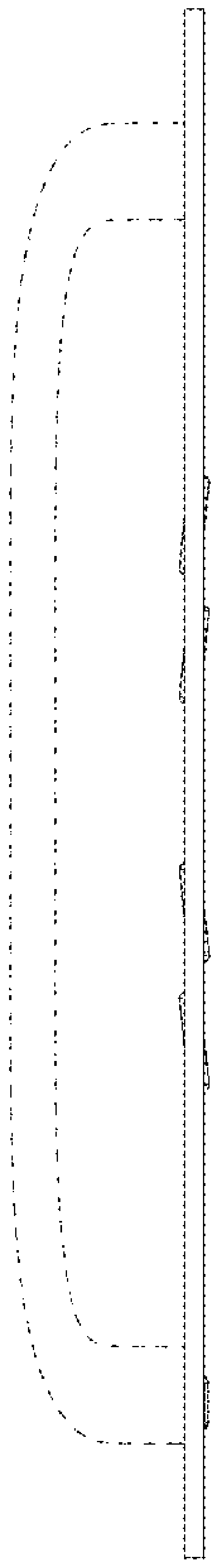

FIG. 5

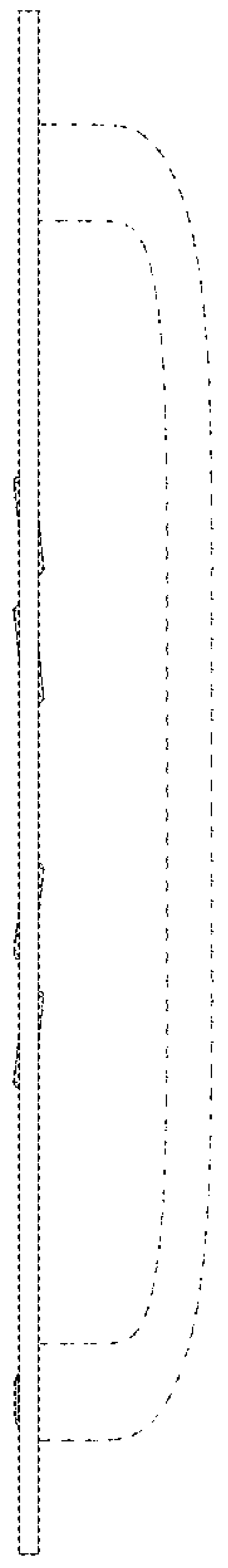

FIG. 6

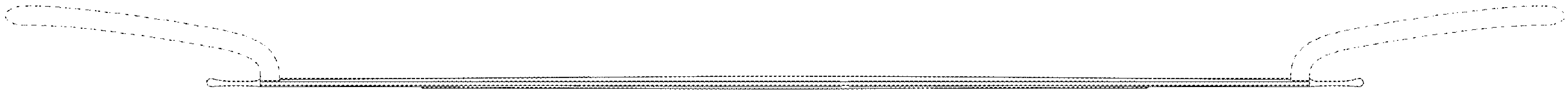

FIG. 7

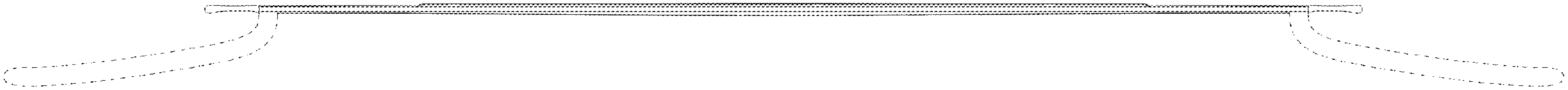

FIG. 8